

IN THE CLAIMS

Please enter the following amended claims: (claims 1-14)

1. (currently amended) An apparatus for forming an alignment layer on a substrate of a liquid crystal display comprising:

an ion source for generating ion beams; and

a mask having a slit and provided placed between the said substrate and the said ion source, wherein said ion source is provided with has a plate-like object with a plurality of ion ejection holes of various sizes having a first area provided with ejection holes of different sizes, and a second area having ejection holes of uniform size, and wherein said first and second areas are arranged in parallel with said slit.

2. (currently amended) The apparatus according to claim 1, wherein the size of said ion ejection holes varies in accordance to depending on the ion density.

3. (currently amended) The apparatus according to claim 2, wherein in said plate-like object, ejection holes in a higher ion density portion of said plate-like object are smaller in size than these the size of the ejection holes in a lower ion density portion of said plate-like object.

4. (currently amended) The apparatus according to any one of claims 1 to 3, wherein said plate-like object has an area with ejection holes of different sizes and an area ejection holes of uniform size is provided with areas of high ion density alternating with areas of low ion density.

5. (currently amended) The apparatus according to claim 4, wherein said alternating areas of high ion density are comprised of ejection holes having a smaller size than the ejection holes in said low ion density of said plate-like object areas are arranged in parallel with said slit.

6. (currently amended) The apparatus according to claim 15, further comprising a stage for moving said substrate, wherein said area with ejection holes of different sizes is provided on a rear the back side relative to the moving direction of the said substrate.

7. (currently amended) An apparatus for forming an alignment layer on a substrate of a liquid crystal display comprising:

an ion source for generating ion beams; and

a mask having a slit and provided between the substrate and the ion source, wherein said ion source has a plate like object with different numbers of ion ejection holes per unit area provided with a first area having different numbers of ejection holes per unit area, and a second area having the same number of ejection holes per unit area, said first and second areas being contiguous to each other and parallel to said slit

8. (original) The apparatus according to claim 7, wherein the number of said ion ejection holes varies depending on the ion density.

9. (currently amended) The apparatus according to claim 8, wherein ~~in said plate-like object~~, a high ion density portion of said plate-like object has a lesser number of ejection holes per unit area than a low ion density portion of said plate-like object.

10. (currently amended) The apparatus according to any one of claims 1 to 3 claim 7, wherein ~~said plate-like object has an area having different numbers of ejection holes per unit area and an area having the same number of ejection holes per unit area~~ ion source is comprised of a plasma generation chamber, a gas inlet for introducing gas into said plasma generation chamber, an accelerating electrode for accelerating said ions in said plasma generation chamber and a grid for ejecting said accelerated ions to the outside.

11. (currently amended) The apparatus according to claim 10 7, wherein said ejection holes areas are arranged in parallel with in said first and second areas are arranged in parallel with the longitudinal direction of said slit.

12. (currently amended) The apparatus according to claim 7 11, further comprising a stage for moving said substrate, wherein said area with first and second areas having ejection holes of different sizes is provided on a rear the back side relative to the moving direction of the substrate.

13. (currently amended) A method for forming an alignment layer on a substrate of a liquid crystal display, comprising the steps of:

generating ion beams at an ion source;
changing the intensity of the ion beams depending on the ion density of the ion source; and
applying said ion beams to a thin film on the said substrate.

14. (currently amended) The method according to claim 13, wherein said step of changing the intensity of the ion beams includes making the intensity of the ion beams uniform by changing both the size and the density of the said ejection holes.